Supporting Information

Photo-Polymerization using Quantum Dots for Stable Epoxy Coatings

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Fig. S1: Mechanism for the photo-polymerization of epoxy in the presence of isopropanol using semiconducting nanoparticles, from Riad et al, 2020.¹







Figure S3: effect of light intensity on epoxy photopolymerization reaction kinetics. Samples consist of epoxy, 1-Phenethyl alcohol (10 wt%), Methyl Viologen (0.5 wt%) and P25 (5 wt%).

¹ K. B. Riad, A. A. Arnold, J. P. Claverie, S. V. Hoa and P. M. Wood-Adams, Photopolymerization using metal oxide semiconducting nanoparticles for epoxy-based coatings and patterned films, *ACS Appl. Nano Mater.*, 2020, **3**, 2875-2880.